

Sub 2 A2
7. (Amended) The washing method according to claim 6, wherein said first ultrasonic wave and said second ultrasonic wave are applied to the thing to be washed at predetermined time intervals.

Sub 1
13. (Amended) A semiconductor device manufacturing method comprising a step of washing a surface at which a pattern including an island-like structure with a width of $0.2 \mu\text{m}$ or less and an aspect ratio of 1.0 or more has been formed by applying a plurality of ultrasonic waves continuously.

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14. (Amended) The semiconductor device manufacturing method according to claim 13, wherein said plurality of ultrasonic waves differs from each other in any one of phase, wavelength, and amplitude.

15. (Amended) A semiconductor device manufacturing method comprising a step of washing a surface at which metal wires are exposed by applying a plurality of ultrasonic waves continuously.

16. (Amended) The semiconductor device manufacturing method according to claim 15, wherein said plurality of ultrasonic waves differs from each other in any one of phase, wavelength, and amplitude.

17. (Amended) A method of manufacturing matrix-type display devices, comprising a step of washing a surface at which Si or metal wires are exposed by applying a plurality of ultrasonic waves continuously.

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18. (Amended) The method according to claim 17, wherein said plurality of ultrasonic waves differs from each other in any one of phase, wavelength, and amplitude.

Please add the following new claims 19-23:

Sub B4

19. (New) The method according to claim 1, wherein said ultrasonic wave is turned on and off repeatedly at specific time intervals.

20. (New) The method according to claim 7, wherein said first step and said second step are repeated continuously.

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21. (New) An ultrasonic washing method comprising a step of washing a thing to be washed by applying a plurality of ultrasonic waves continuously.

22. (New) The washing method according to claim 21, wherein said ultrasonic waves are applied to the thing to be washed at predetermined time intervals.

23. (New) The washing method according to claim 22, wherein said ultrasonic waves differ from each other in any one of phase, wavelength, and amplitude.

REMARKS

Applicant has amended claims 1, 7, and 13-18 to improve form and not for any reason related to patentability. Applicant has also added new claims 19-23 to protect further aspects of the invention. No new matter has been introduced by these amendments.